



Three Patent Application of

Group Art Unit: 1763

Examiner: JEFFRIE ROBERT LUND

Confirmation No.: 3621

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**Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450**

In accordance with the duty of disclosure as set forth in 37 C.F.R. § 1.56, the accompanying information is being submitted in accordance with 37 C.F.R. §§ 1.97 and 1.98.

All of the listed documents were previously made of record in prior Application Serial No. 10/043,190, now U.S. Patent No. 6,758,224, filed January 14, 2002, upon which Applicants rely for the benefits provided in 35 U.S.C. § 120.

The documents are being submitted after a first Office Action on the merits but prior to the closing of prosecution, therefore under 37 C.F.R. § 1.97(c), the fee set forth in 37 C.F.R. § 1.17(p) is enclosed.


A fee of \$180.00 (1806) as set forth in 37 C.F.R. § 1.17(p) is enclosed.

To assist the Examiner, the documents are listed on the attached form PTO-1449. It is respectfully requested that an Examiner initialed copy of this form be returned to the undersigned.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

Date 3-2-05

By: 
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Substitute for form 1449A/PTO & 1449B/PTO		Complete if Known	
FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT <small>(use as many sheets as necessary)</small>		Application Number	10/709,622
		Filing Date	May 18, 2004
		First Named Inventor	Hiroshi Nogami
		Examiner Name	JEFFRIE ROBERT LUND
Sheet	1 of 2	Attorney Docket Number	001425-126

U.S. PATENT DOCUMENTS				
Examiner Initials	Document Number	Kind Code (if known)	Name of Patentee or Applicant of Cited Document	Issue/Publication Date (MM-DD-YYYY)
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	4,792,378		Rose et al.	12-20-1998
	5,336,326		Karner et al.	08-09-1994
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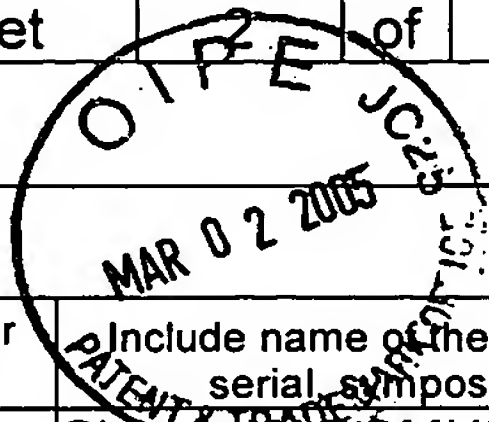
FOREIGN PATENT DOCUMENTS											
Examiner Initials	Document Number	Kind Code (if known)	Country	Date of Publication (MM-DD-YYYY)	STATUS						
					Translation	Partial Translation	Eng. Lang. Summary	Search Report	IPER	Abstract	Cited in Spec
	7-201749		Japan	08-04-1995							
	2837087		Japan	10-09-1998							
	6-260434		Japan	09-16-1994						X	
	5-21393		Japan	01-29-1993						X	

Examiner Signature		Date Considered	
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

VA 696207.1

Substitute for form 1449A/PTO & 1449B/PTO		Complete if Known		
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		Filing Date	May 18, 2004	
		First Named Inventor	Hiroshi Nogami	
		Examiner Name	JEFFRIE ROBERT LUND	
Sheet	2	of	Attorney Docket Number	001425-126



NON-PATENT LITERATURE DOCUMENTS	
Examiner Initials	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
	Shingo KADOMURA et al., "ANISOTROPIC ETCHING USING DEPOSITION OF SULFUR, Sony Corporation, Semiconductor World, January 1993, pp. 1-11, and translation
	Ken FUJITA et al., "X-RAY PHOTOELECTRON SPECTROSCOPIC STUDIES ON PYROLYSIS OF PLASMA-POLYMERIZED FLUOROCARBON FILMS ON Si", Jpn. J. Appl. Phys. volume 34 (1995), pp. 304-306, Part 1, NO. 1, January 1995
	Robert C. REID et al., "THE PROPERTIES OF GASES AND LIQUIDS", McGraw-Hill, Inc., Appendix B, Index
	R. Byron BIRD et al., "TRANSPORT PHENOMENA", Jon Wiley & Sons, pp. 508-509 and 512-513
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	Robert C. REID et al. "Lennard-Jones Potentials as Determined from Viscosity Data (Appendix B)", <i>The Properties of Gases and Liquids</i> , McGraw-Hill, Inc., Copyright 1987, p.734, Index
	R. Byron BIRD et al. "Diffusivity and the Mechanisms of Mass Transport; Theory of Ordinary Diffusion in Gases at Low Density", <i>Transport Phenomena</i> , John Wiley & Sons, Inc., Copyright 1960, p. 508-513
	A new technique for diagnostics of a radio-frequency parallel-plate remote plasma; N. Sano et al.; Appl. Phys. Lett 65 (2), 11 July 1994 pages 162-164.
	Infrared spectroscopic study of SiO _x films produced by plasma enhanced chemical vapor deposition; J. Vac.Sci. Technol. A4(3), May/June 1986; pages 689-694.
	Improvement of structural and electrical properties in low-temperature gate oxides for poly-Si TFTs by controlling O ₂ /SiH ₄ ratios; AM-LCD 1997; pages 87-90.
	"Flow of Atoms and Molecules—Rarefied Gas Dynamics and its Applications", section 2.6.4, The Japan Society of Mechanical Engineers, 1996, Kyoritsu Shuppan Co., Ltd.

Examiner Signature		Date Considered	
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VA 696207.1